

	L #	Hits	Search Text
1	L1	4	944145.ap.
2	L2	41299	(mask or reticle) and (lithography or photolithography or photo-lithography)
3	L3	16290	(substrate or wafer) same (focus or focal)
4	L4	209937	((projection near optical) or (lens or optical)) same (adjust\$4 or move or moving or moved or rotat\$3 or translat\$3 or manipul\$3)
5	L5	24068	(correct\$3 or adjust\$4 or compensat\$3) with (focus or (focal near2 plane))
6	L6	794	2 and 3 and 4 and 5
7	L7	615	6 and (355/\$.ccls. or 430/\$.ccls. or 356/\$.ccls. or 250/\$.ccls.)
8	L8	2144	(substrate or wafer) same (plane near2 focal)
9	L9	177	2 and 8 and 4 and 5
10	L10	142	9 and (355/\$.ccls. or 430/\$.ccls. or 356/\$.ccls. or 250/\$.ccls.)
11	L11	123	9 and (355/\$.ccls. or 430/\$.ccls. or 356/\$.ccls.)


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	L #	Hits	Search Text
12	L12	145316	((projection near optical) or (lens or optical)) with (adjust\$4 or move or moving or moved or rotat\$3 or translat\$3 or manipul\$3)
13	L13	14149	(correct\$3 or adjust\$4 or compensat\$3) with (focus or (focal near2 plane)) with ((projection near optical) or (optical or lens))
14	L14	13177	12 and 13
15	L15	498	2 and 3 and 14
16	L16	290	15 and (355/\$.ccls. or 430/\$.ccls. or 356/\$.ccls.)
17	L17	2878	(chang\$3 or adjust\$4 or correct\$3) with (focal near plane)
18	L18	66	11 and 17
19	L19	71	(map\$4) with height with (wafer or substrate)
20	L20	680	(stor\$3 or memor\$6 or map\$4) with (height or (surface near contour)) with (wafer or substrate)
21	L21	168	20 and 2
22	L22	30	21 and (355/\$.ccls. or 430/\$.ccls. or 356/\$.ccls.)

	L #	Hits	Search Text
23	L23	24068	(correct\$3 or adjust\$4 or compensat\$3) with (focus or (focal near2 plane))
24	L24	18	22 and 23